

55. The method of claim 54 wherein the antihalation composition layer is crosslinked prior to applying the photoresist composition.

56. The method of claim 54 wherein the antireflective composition comprises a thermal acid generator.

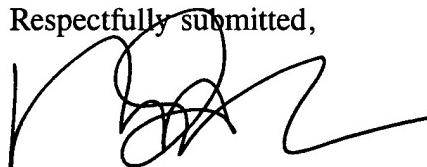
57. The method of claim 54 wherein the substrate is a microelectronic wafer.

REMARKS

Claims 1-35 have been cancelled without prejudice, and claims 36-57 have been added. No new matter has been added by virtue of the amendments. For instance, support for the new claims appears e.g. page 8 and the original claims of the application.

Early consideration and allowance of the application are respectfully requested.

Respectfully submitted,


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MARKED UP VERSION TO SHOW CHANGES

20. (amended) A coated substrate comprising:
a substrate having thereon
- 1) a coating layer of an antireflective composition of claim 18 [17]; and
 - 2) a coating layer of a photoresist.

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